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Atty. Docket No. KOV-012 Serial No: 10/749,876

Amendments to the Claims

Please amend Claims 3, 4, 6, 10, 13, 14, 16, 17, 18, 19, 20, 21, 22, 23, 24, 38, 67, and 68 as shown below and cancel Claims 1, 2, 12, 26, 64, 65, 66, 69, 70, 71, 72, and 73. This listing of Claims replaces all prior versions and listings of the Claims in this application.

Listing of the Claims

- 1. (Canceled)
- 2. (Canceled)
- 3. (Currently Amended) The material of Claim + 21, wherein said electronically functional substance comprises a metal that absorbs a first wavelength of UV light.
- (Currently Amended) The material of Claim 1 21, wherein said electronically functional substance comprises one or more members of the group consisting of silicon, germanium, CdS, CdSe, InP, InAs and GaAs.
- 5. (Original) The material of Claim 4, wherein said electronically functional substance comprises silicon.
- 6. (Currently Amended) The material of Claim + 9, wherein said electronically functional substance comprises one or more members of the group consisting of transition metals, noble metals, aluminum, indium, tin, lead, and alloys thereof.
- 7. (Original) The material of Claim 6, wherein said electronically functional substance comprises one or more members of the group consisting of Cr, Mo, W, Fe, Ru, Ni, Pd, Pt, copper, silver, gold, and aluminum.

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- 8. (Original) The material of Claim 7, wherein said electronically functional substance comprises nickel, copper, silver or gold.
- 9. (Previously presented) The material of Claim 3, wherein said photoreactive group or group that is reactive with said photochemically generated species absorbs a second wavelength of UV light significantly different from said first wavelength of UV light.
- 10. (Currently amended) The material of Claim 1 9, wherein said ligands Y contains a group that is reactive with said photochemically generated species and that, after reacting with said photochemically generated species, materially changes the solubility characteristics of said material in said developer.
- 11. (Previously presented) The material of Claim 10, wherein said photoreactive group comprises a quinone, and said ligand comprises a phonol.
- 12. (Canceled)
- 13. (Currently amended) The material of Claim 12 21, wherein said ligands are bound to said nanoparticles through at least one nanoparticle-binding group is a member selected from the group consisting of an alcoholate, a thiolate, a disulfide, a carboxylate, a carboxylic acid, an amine, a phosphine, a phosphine oxide and an alkyl group.
- 14. (Currently amended) The material of Claim ‡ 21, wherein Y is said group that is reactive with said photochemically generated species, and is selected from the group consisting of a carbon-carbon double bond, an epoxide, an oxirane, an aziridine, a phenol, a carbonate and a carbamate.

- 15. (Original) The material of Claim 14, wherein said group that is reactive with said photochemically generated species comprises said carbon-carbon double bond, and said carbon-carbon double bond is selected from the group consisting of a vinyl group, an activated carbon-carbon double bond, an acrylate, and a vinyl ketone.
- 16. (Currently amended) The material of Claim 4 21, wherein said nanoparticle[[s]] have has an average diameter of less than 100 nm.
- 17. (Currently amended) The material of Claim + 21, wherein said nanoparticle[[s]] have has an average diameter of less than 10 nm.
- 18. (Currently amended) The material of Claim 121, wherein said nanoparticle[[s]] have has an average diameter of less than 5 nm.
- 19. (Currently amended) The material of Claim 4 21, wherein said photochemically generated species has an ultraviolet absorption maximum at a first wavelength and said nanoparticle[[s]] have has an ultraviolet absorption maximum at a second wavelength, said second wavelength significantly differing from said first wavelength.
- 20. (Currently amended) The material of Claim 19, wherein said photoreactive group comprises an azide, said first wavelength is one at which a mercury arc lamp has a relatively strong irradiance, and said nanoparticle[[s]] comprises a metal having a relatively poor absorbance at said first wavelength.
- 21. (Currently amended) The material of Claim 1 A radiation patternable functional material, comprising a compound of the formula (1):

$$(R^1-X^1)_mNP(X^2-R^2-Y)_n,$$
 (1)

where NP comprises <u>a said</u> nanoparticle of <u>an said</u> electronically functional substance selected from the group consisting of semiconductors and metal; Y is <u>a said</u> group that is photoreactive or that is reactive with <u>a said</u> photochemically generated species <u>and</u> which, after first-order photoreaction or reacting with said photochemically generated species, materially changes the solubility characteristics of said compound in a developer; X^1 and X^2 are independently a nanoparticle-binding group; R^1 is a monovalent group that is not reactive with said photochemically generated species; R^2 is a divalent bridging group; m is at least 0, and the m instances of R^1 - X^1 may be the same or different; and n is at least 1, and the n instances of X^2 - R^2 -Y may be the same or different; and m + n is at least 2; wherein, after irradiation, developing and curing, the functional material forms a patterned film of an electronically conducting or semiconducting material.

- 22. (Currently amended) The material ink of Claim 3 38, further comprising wherein said nanoparticles comprise a member of the group consisting of passivated nanoparticles and nanoparticles containing ligands not having a (photo) reactive group bound thereto.
- 23. (Currently amended) The material of Claim 22 21, wherein said electronically functional substance consists essentially of silicon and/or germanium.
- 24. (Currently amended) The material of Claim 22 21, wherein said electronically functional substance comprises one or more members of the group consisting of transition metals, noble metals, aluminum, indium, tin, lead, and alloys thereof.
- 25. (Previously presented) The material of Claim 24, wherein said electronically functional substance consists essentially of nickel, copper, silver or gold.
- 26. (Canceled)

- (Previously presented) The material of Claim 21, wherein R¹ is alkyl, cycloalkyl, aryl or 27. aralkyl, any one of which may be substituted one or more times with a halogen or with a substituent selected from the group consisting of alkyl (except where R1 = alkyl), cycloalkyl, aryl, aralkyl (except where R1 = alkyl), alkoxy, alkylthio, alkylcarbonyl, alkoxycarbonyl, alkylcarboxy, alkylamino, dialkylamino, alkylamido, dialkylamido, cycloalkoxycarbonyl, cycloalkylcarbonyl, cycloalkylthio, cycloalkoxy, cycloalkylcarboxy, cycloalkylamino, di(cycloalkyl)amino, (cycloalkyl)(alkyl)amino, cycloalkylamido, di(cycloalkyl)amido, (cycloalkyl)(alkyl)amido, aryloxy, arylthio, arylcarbonyl, aryloxycarbonyl, arylcarboxy, arylamino, diarylamino, (aryl)(alkyl)amino, arylamido, aralkoxy, aralkylthio, aralkylcarbonyl, aralkoxycarbonyl, aralkylcarboxy, aralkylamino, diaralkylamino, (aralkyl)(alkyl)amino, heterocyclyl, trialkylsilyl, and trialkylsilyloxy, each of which may be further substituted with one or more halogens, alkyl groups (except for alkyl substituents on R1) and/or alkoxy groups.
- 28. (Previously presented) The material of Claim 27, wherein R¹ is C₄-C₂₀ alkyl which may be substituted one or more times with a halogen, a C₁-C₆ alkoxy, C₃-C₈ cycloalkyl, phenyl and/or C₇-C₂₀ aralkyl, each of which (except for halogen) may be further substituted with one or more halogens, C₁-C₆ alkyl groups and/or C₁-C₆ alkoxy groups.
- (Previously presented) The material of Claim 21, wherein R² is selected from the group 29. consisting of alkylene, alkyleneoxy, alkyleneoxyalkylene, alkyleneoxyalkyleneoxy, alkylenethioalkylene, alkylenecarbonyl, alkyleneoxycarbonyl, alkylenethio, alkylenecarboxy, alkyleneamino, alkylene(alkyl)amino, alkylene(alkyl)aminoalkylene, alkylenc(alkyl)amido, cycloalkylene, cycloalkylencoxy, alkyleneamido, cycloalkyleneoxycarbonyl, cycloalkylenecarbonyl, cycloalkylenethio, (cycloalkylene)(alkyl)amino, cycloalkyleneamino, cycloalkylenecarboxy, cycloalkyleneamido, (cycloalkylene)(alkyl)amido, arylene, alkylene-arylene, alkylenealkyleneoxyarylene, alkylene-aryleneoxy, arylene-alkylene, aryleneoxy, arylenethioalkylene, arylenethio, alkylene-arylenethio, aryleneoxyalkylene,

> alkylene-arylenecarbonyl, aryleneoxycarbonyl, alkylenearylenecarbonyl, aryleneoxycarbonyl, arylenecarboxy, alkylene-arylenecarboxy, aryleneamino, alkylenearyleneamino, arylene(aryl)-amino, alkylene-arylene(aryl)amino, arylene(alkyl)amino, alkylene(aryl)amino, aryleneamido, aralkylene, alkylene-arylene(alkyl)amino, aralkylenecarbonyl, aralkylenethio, (alkylene)aralkyleneoxy, aralkyleneoxy, aralkyleneoxycarbonyl, aralkylenecarboxy, aralkyleneamino, aralkylene(aryl)amino, alkylene-(alkylene)(aralkyl)amino, heterocyclylene, (aralkylene)(alkyl)amino, heterocyclylene, and alkylene-heterocyclylene-alkylene, cach of which may be further substituted with one or more halogens, alkyl groups (except where R^2 = alkylene), alkoxy groups, trialkylsilyl, and/or trialkylsilyloxy groups.

- (Previously presented) The material of Claim 29, wherein R² is selected from the group 30. consisting of alkylene, alkylene substituted with one or more halogens and/or alkoxy alkylcneoxyalkyleneoxy, alkyleneoxyalkylene, groups, alkyleneoxy, alkylene(alkyl)amino, cycloalkylene, arylene, arylene substituted with one or more aryleneoxy, arylenethio, halogens, alkyl groups and/or alkoxy groups, arylene(alkyl)amino, aralkylene, (alkylene)aralkylene, and aralkylene(alkyl)amino.
- 31. (Previously presented) The material of Claim 30, wherein R² is selected from the group consisting of C₄-C₂₀, branched or unbranched, saturated or unsaturated alkylene groups; C₇-C₁₇, branched or unbranched, substituted or unsubstituted aralkylene groups; C₄-C₂₀, branched or unbranched, saturated or unsaturated alkyleneoxy groups; and C₄-C₂₀, branched or unbranched, saturated or unsaturated alkylene thio groups.
- 32. (Previously presented) The material of Claim 21, wherein Y is reactive with a photochemically generated species and which, after reacting with said photochemically generated species, materially changes the solubility characteristics of said material in said developer.

- (Previously presented) The material of Claim 32, wherein Y is selected from the group 33. consisting of a carbon-carbon double bond, an epoxide, an oxirane, an aziridine, and a phenol.
- (Previously presented) The material of Claim 32, wherein Y is selected from the group 34. consisting of a vinyl group, a vinylidene group, an epoxide, a carbonate, a carbamate and a phenol.
- (Previously presented) The material of Claim 34, wherein Y comprises a vinyl group or a 35. vinylidene group substituted with a halogen, a C1-C6 alkyl group, a C1-C6 alkoxy group, a phenyl group, a phenyl group substituted with one or more halogens, C1-C6 alkyl groups, C1-C6 alkoxy groups and/or di-(C1-C6 alkyl)amino groups, a -C(=O)-C1-C6 alkyl group, a -C(=O)-C₁-C₆ alkoxy group, or a cyano group.
- (Previously presented) The material of Claim 21, wherein X^1 and X^2 are independently a 36. chalcogen, a carboxylate group, a carboxylic acid group, a thiocarboxylate group, a thiocarboxylic acid group, an alkylene group, NR5 u (where u is from 0 to 2 and each R5 is independently H or a C₁-C₆ alkyl group), S(O)_x (where x is from 1 to 3), PR⁷_v (where v is from 0 to 3 and each R7 is independently H, a C1-C6 alkyl group or a C6-C10 aryl group which may be substituted with one or more halogen, C1-C4 alkyl, C1-C4 alkoxy, or di-C1-C₄ alkylamino groups) or P(O)_y(R⁶)_z (where y is from 1 to 3, z is 1 or 2, and each R⁶ is independently H, phenyl or a C1-C6 alkyl group).
- (Previously presented) The material of Claim 36, wherein X1 and X2 are independently 37. at least one nanoparticle-binding member is selected from the group consisting of O, S, a carboxylate, a carboxylic acid group, and a -CH₂CH₂- group.

- 38. (Currently amended) A radiation definable ink, comprising:
 - a) the material of Claim 1 a radiation patternable functional material, comprising nanoparticles of an electronically functional substance selected from the group consisting of semiconductors and metals, and a plurality of ligands bound to each of said nanoparticles, said ligands containing a photoreactive group or a group that is reactive with a photochemically generated species and that, after first-order photoreaction or reacting with said photochemically generated species, materially changes the solubility characteristics of said material in a developer, wherein, after irradiation, developing and curing, the functional material forms a patterned film of an electronically conducting or semiconducting material; and
- b) a solvent in which said material is soluble.
- 39. (Previously presented) The ink of Claim 38, further comprising a source of said photochemically generated species.
- 40. (Previously presented) The ink of Claim 39, wherein said source of said photochemically generated species is selected from the group consisting of azides, photogenerated acid sources, photogenerated radical sources, carbonates, carbamates, and quinones.
- 41. (Previously presented) The ink of Claim 39, wherein said source of said photochemically generated species is an azide, and said group that is reactive with said photochemically generated species comprises said carbon-carbon double bond.
- 42. (Previously presented) The ink of Claim 39, wherein said source of said photochemically generated species is a photogenerated acid source, and said group that is reactive with said photochemically generated species is selected from the group consisting of an epoxide, an oxirane, an aziridine, and an activated carbon-carbon double bond.

- 43. (Previously presented) The ink of Claim 39, wherein said source of said photochemically generated species is a photogenerated radical source, and said group that is reactive with said photochemically generated species comprises an acrylate.
- 44. (Previously presented) The ink of Claim 38, wherein said ligands contain said photochemically reactive group, and said photochemically reactive group comprises a carbonate and/or a carbamate.
- 45. (Previously presented) The ink of Claim 38, wherein said photoreactive group comprises a quinone, and said ligand comprises a phenol.
- 46. (Previously presented) The ink of Claim 38, wherein said material is present in said ink in a percentage by weight of from 0.1% to 50%.
- 47. (Previously presented) The ink of Claim 38, wherein said solvent is selected from the group consisting of alkanes, alkenes, halogenated alkanes, halogenated alkanes, arenes, substituted arenes, alcohols, ethers, cyclic ethers, aliphatic ketones, aliphatic esters, aliphatic amides and aliphatic sulfoxides.
- 48. (Previously presented) The ink of Claim 47, wherein said solvent is selected from the group consisting of C₆-C₂₀ alkanes, C₆-C₂₀ alkenes, benzene which may be substituted with from 1 to 3 C₁-C₄ alkyl groups, C₁-C₆ aliphatic alcohols, C₄-C₂₀ ethers, C₄-C₂₀ polyethers, C₄-C₁₀ aliphatic ketones, and C₁-C₆ aliphatic esters of C₂-C₁₂ aliphatic carboxylic acids that may be substituted with from 1 to 3 halogen atoms or a C₁-C₄ alkoxy group.
- 49. (Previously presented) The ink of Claim 48, wherein said solvent comprises propylene glycol methyl ether acetate or ethyl ethoxypropionate.

- 50. (Previously presented) The ink of Claim 47, further comprising one or more additives selected from the group consisting of a tension reducing agent, a surfactant, a thickening agent, and an adhesion promoter.
- 51. (Previously presented) The ink of Claim 50, further comprising said adhesion promoter.
- 52. (Previously presented) The ink of Claim 51, wherein said adhesion promoter comprises a C₆-C₂₀, branched or unbranched, mono- or polyunsaturated alkene; a C₈-C₁₈, branched or unbranched, substituted or unsubstituted mono- or polyunsaturated aralkene; a C₄-C₂₀, branched or unbranched, mono- or polyunsaturated alkenoic acid; a C₁-C₂₀ branched or unbranched aliphatic alcohol ester of a C₂-C₂₀, branched or unbranched aliphatic acid, wherein at least one of said aliphatic alcohol and said aliphatic acid contains at least 3 carbon atoms and at least one site of unsaturation; and/or a C₄-C₂₀, branched or unbranched, mono- or polyunsaturated aliphatic alcohol or aliphatic mercaptan.
- 53. (Previously presented) A radiation definable ink, comprising:
 - a) the material of Claim 21; and
 - b) a solvent in which said compound is soluble.
- 54. (Previously presented) The ink of Claim 53, further comprising a source of said photochemically generated species.
- 55. (Previously presented) The ink of Claim 54, wherein said source of said photochemically generated species is selected from the group consisting of azides, photogenerated acid sources, photogenerated radical sources and quinones.

- 56. (Previously presented) The ink of Claim 54, wherein said source of said photochemically generated species is an azide, and said group that is reactive with said photochemically generated species comprises said carbon-carbon double bond.
- 57. (Previously presented) The ink of Claim 54, wherein said source of said photochemically generated species comprises a photogenerated acid source, and said group that is reactive with said photochemically generated species is selected from the group consisting of an epoxide, an oxirane, an aziridine, and an activated carbon-carbon double bond.
- 58. (Previously presented) The ink of Claim 54, wherein said source of said photochemically generated species comprises a photogenerated radical source, and said group that is reactive with said photochemically generated species comprises an acrylate.
- 59. (Previously presented) The ink of Claim 53, wherein said ligands contain said photochemically reactive group, and said photochemically reactive group comprises a carbonate and/or a carbonate.
- 60. (Previously presented) The ink of Claim 53, wherein said compound is present in said composition in a percentage by weight of from 0.1% to 50%.
- 61. (Previously presented) The ink of Claim 53, further comprising one or more additives selected from the group consisting of a tension reducing agent, a surfactant, a thickening agent, and an adhesion promoter.
- 62. (Previously presented) The ink of Claim 61, further comprising said adhesion promoter.
- 63. (Previously presented) The ink of Claim 62, wherein said binder comprises a C₆-C₂₀, branched or unbranched, mono- or polyunsaturated alkene; a C₈-C₁₈, branched or

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unbranched, substituted or unsubstituted mono- or polyunsaturated aralkene; a C₄-C₂₀, branched or unbranched, mono- or polyunsaturated alkenoic acid; a C₁-C₂₀ branched or unbranched aliphatic alcohol ester of a C₂-C₂₀, branched or unbranched aliphatic acid, wherein at least one of said aliphatic alcohol and said aliphatic acid contains at least 3 carbon atoms and at least one site of unsaturation; and/or a C₄-C₂₀, branched or unbranched, mono- or polyunsaturated aliphatic alcohol or aliphatic mercaptan.

- 64. (Canceled)
- 65, (Canceled)
- 66. (Canceled)
- (Currently amended) The method of Claim 65 75, wherein said reacting comprises comprising mixing (1) said nanoparticles of said electronically functional substance containing said ligands not having said photococcutive group or said group that is reactive with said photochemically generated species bound thereto and (2) said non-ligated compound[[s]] in a solvent for a length of time sufficient to exchange at least a portion of the non-ligated compound[[s]] for said ligands bound to said nanoparticles and not having said photoceactive group or said group that is reactive with said photochemically generated species bound thereto.
- 68. (Currently amended) The method of Claim 67, wherein said ligands bound to said nanoparticles and not having said photoreactive group or said group that is reactive with said photochemically generated species bound thereto are present in an excess molar amount with respect to said nanoparticles.
- 69. (Canceled)

- 70. (Canceled)
- 71. (Canceled)
- 72. (Canceled)
- 73. (Canceled)
- 74. (Previously presented) A method of making the material of Claim 21, comprising the steps of
 - a) mixing nanoparticles of the formula NP(X¹-R¹)_k, where k is an integer greater han 1 and where NP, X¹ and R¹ are as defined in Claim 21, with a molar excess of a compound of the formula HX²-R²-Y or a salt thereof, where X², R² and Y are as defined in Claim 21, in a reaction mixture; and
 - b) isolating and/or purifying said compound of the formula (1) from said reaction mixture.
- 75. (Previously presented) The method of Claim 74, further comprising mixing a Lewis base with said nanoparticles of the formula NP(X¹-R¹)_k and said compound of the formula HX²-R²-Y to promote a ligand exchange.
- 76. (Previously presented) The method of Claim 74, wherein said compound of the formula H-X²-R²-Y or a salt thereof is present in at least 4 times the molar amount of said nanoparticles.
- 77. (Previously presented) The method of Claim 74, wherein R¹-X¹ is R¹-C(=O)-O-, and H-X²-R²-Y is H-S-R²-Y.

- 78. (Previously presented) A method of making the material of Claim 21, comprising
 - a) either:
 - i) mixing nanoparticles of the formula $(R^1-X^1)_mNP(X^2-R^3-Z)_n$, where R^3 is any R^2 group, Z is a leaving group or electrophile, and NP, m, n, X^1 , X^2 , R^1 and R^2 are as defined in Claim 21, with a compound of the formula H-Y, H-Nu-Y, H-Nu-R⁴-Y or a salt of such compounds, where Nu is a conventional nucleophile and R^4 is R^2 minus R^3 , and Y is as defined in Claim 21, in a reaction mixture, or
 - ii) mixing nanoparticles of the formula $(R^1-X^1)_mNP(X^2-R^3-Nu-H)_n$ or a salt thereof with a compound of the formula Z-Y or Z-R⁴-Y in a reaction mixture, where R^1 , R^3 , R^4 , NP, m, n, X^1 , X^2 , Nu, Y and Z are as defined above; and
 - isolating and/or purifying said compound of the formula (1) from said reaction mixture.
- 79. (Previously presented) The method of Claim 78, wherein said nanoparticles have the formula $(R^1-X^1)_mNP(X^2-R^3-OH)_n$, $(R^1-X^1)_mNP(X^2-R^3-COOR^5)_n$, $(R^1-X^1)_mNP(X^2-R^3-NZ_2)_n$, or $(R^1-X^1)_mNP(X^2-R^3-SH)_n$, X^2 is independently a carboxylate, a carboxylic acid, $-NR^8_2$, $-N^4R^8_3$, an oxygen atom or sulfur atom, R^8 is H or alkyl, and R^5 is H or an ester protecting group.
- 80. (Previously presented) The method of Claim 78, wherein said mixing comprising mixing nanoparticles of the formula $(R^1-X^1)_mNP(X^2-R^3-Z)_n$, where NP consists essentially of a metal and X^2 is a carboxylate, a carboxylic acid or S, with said compound of the formula H-Nu-Y, H-Nu-R⁴-Y or a salt thereof, where NuH is -NHR⁸, OH or SH (except that NuH is OH when X^2 is said carboxylate or carboxylic acid) and X^3 is H or alkyl.
- 81. (Previously presented) The method of Claim 78, wherein NP consists essentially of silicon or a silicon-germanium mixture, X² is alkylene or O, and said compound of the

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> formula H-Y, H-Nu-Y, or H-Nu-R⁴-Y is either H-Nu-Y or H-Nu-R⁴-Y, where H-Nu is COOH, NHR⁸ or SH, and R⁸ is H or alkyl.

- (Previously presented) The method of Claim 78, comprising mixing nanoparticles of the 82. formula (R¹-X¹)_mNP(X²-R³-Z)_n with a compound of the formula H-Y or a salt thereof.
- (Previously presented) The method of Claim 78, wherein Y is a cyanide, azide, 83. hydroxide or sulfide anion.
- (Previously presented) The method of Claim 78, comprising mixing nanoparticles of the 84. formula (R¹-X¹)_mNP(X²-R³-Nu-H)_n or a salt thereof with a compound of the formula Z-Y or $Z-R^4-Y$.
- (Previously presented) The method of Claim 84, wherein Nu comprises a chalcogenide 85. atom, a phenolate anion, an amine, a carboxylate or an aryl group, and said compound of the formula Z-Y or Z-R⁴-Y comprises an aliphatic carboxylic acid anhydride, an allyl halide, or an aliphatic acyl chloride.
- (Previously presented) A method of making the material of Claim 21, comprising the 86. steps of
 - reacting nanoparticles of the formula (R¹-X¹)_mNP(X¹-R³-(CR=CR'R"))_k, where k a) is an integer greater than 1, NP, R1 and X1 are as defined in Claim 21, R3 is R2 or a precursor thereof, and R, R' and R" are independently H, C1-C6 alkyl, C2-C6 alkenyl, C1-C₆ alkoxy, mono- or di-C₁-C₆ alkyl amino, a cyclic amino group, C₆-C₁₀ aryl (which may be substituted one or more times with C1-C6 alkyl, C2-C6 alkenyl, C1-C6 alkoxy, mono- or di-C₁-C₆ amino or halogen); -C(=O)O-C₁-C₆ alkyl or -C(=O)C₁-C₆ alkyl, with an epoxidizing agent or source of Y+, Y or Y-; and

- b) isolating and/or purifying said compound of the formula (1) from said reaction mixture.
- 87. (Previously presented) The method of Claim 86, wherein R, R' and R" are independently H or C₁-C₆ alkyl.
- 88. (Previously presented) The method of Claim 86, wherein said reacting is with said epoxidizing agent.
- 89. (Previously presented) The method of Claim 86, wherein said reacting is with said Y source and comprises electrophilically adding Y from Z-Y to the CR=CR'R" group.
- 90. (Previously presented) The method of Claim 86, wherein said reacting is with said Y source and comprises electrophilically adding HY to the CR=CR'R" group.
- 91. (Previously presented) The method of Claim 86, wherein said reacting is with said Y-source and comprises radical addition of Y from HY or Y₂ to the CR=CR'R" group.
- 92. (Previously presented) A method of making an electronically functional thin film, comprising the steps of:
 - a) irradiating the ink of Claim 38 to form an irradiated composition; and
 - b) curing said irradiated composition to form said electronically functional thin film.
- 93. (Previously presented) The method of Claim 92, further comprising, after said irradiating step and before said curing step, the step of developing said irradiated composition to form a patterned thin film.

- 94. (Previously presented) The method of Claim 93, wherein said irradiating step comprises selectively irradiating portions of said composition, and said developing step comprises removing either irradiated or non-irradiated portions of said layer to form said patterned thin film.
- 95. (Previously presented) The method of Claim 94, wherein said selectively irradiating substep comprises (i) positioning at least one of said substrate and a mask such that said portions can be selectively irradiated and said non-irradiated portions cannot be irradiated, and (ii) irradiating said layer with ultraviolet light through said mask.
- 96. (Previously presented) The method of Claim 92, wherein said composition comprises metal or semiconductor nanoparticles having passivation thereon and/or containing ligands not having a (photo) reactive group bound thereto.
- 97. (Previously presented) The method of Claim 96, wherein said nanoparticles comprise metal nanoparticles.
- 98. (Previously presented) The method of Claim 93, wherein said curing step comprises sintering said developed film to form a patterned electronically functional thin film.
- 99. (Previously presented) The method of Claim 93, wherein said curing step comprises heating said composition to a temperature of at least about 100 °C for a period of time sufficient to remove substantially all of said ligand(s).
- 100. (Previously presented) The method of Claim 99, wherein said curing temperature is at least about 200 °C.

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- (Previously presented) The method of Claim 100, wherein said curing temperature is at 101. least about 300 °C.
- (Previously presented) The method of Claim 101, wherein said curing temperature is at 102. least about 400 °C.
- (Previously presented) The method of Claim 99, further comprising heating said 103. electronically functional thin film to a temperature of at least about 200 °C in the presence of a reducing atmosphere to passivate said electronically functional thin film.
- (Previously presented) The method of Claim 103, wherein said heating temperature is at 104. least about 300 °C.
- (Previously presented) The method of Claim 92, further comprising depositing said 105. composition on a substrate.
- (Previously presented) The method of Claim 105, wherein said depositing comprises 106. inkjetting, spin coating, dip coating, meniscus, extrusion or spray coating a solution, emulsion or suspension of said composition on said substrate.
- (Previously presented) The method of Claim 92, wherein said curing step further 107. comprises placing said substrate into a chamber, and evacuating said chamber.
- (Previously presented) The method of Claim 107, wherein said curing step further 108. comprises passing an inert and/or reducing gas into said chamber.
- (Previously presented) The method of Claim 93, wherein said patterned thin film 109. comprises a two-dimensional array of lines having a width of from 100 nm to 100 µm.

- 110. (Previously presented) The method of Claim 109, wherein said lines have an inter-line spacing of from 100 nm to 100 μ m.
- 111. (Previously presented) The method of Claim 110, wherein said lines have a length of from 1 μm to 5000 μm .
- 112. (Previously presented) The method of Claim 109, wherein said lines have a thickness of from 0.01 μm to 100 μm .

113-123. (Canceled)